

## ABSTRACT

An apparatus comprising:

(a) a substrate including a level intermediate region disposed between a first end region and a second end region;

(b) a first external member disposed circumferentially around the first end region in a continuous manner and protruding above the level intermediate region, thereby resulting in a deposition region including the surface of the first external member covering the first end region, an optional exposed first end region portion, and the intermediate region; and

(c) a dip coated layer over the entire deposition region, wherein the portion of the dip coated layer over the first external member and the optional exposed first end region portion is formed prior to the portion of the dip coated layer over the intermediate layer.